

ABSTRACT

With a conventional organic light emitting element, the pixel formation accuracy is controlled by the pattern formation accuracy of an electrode provided on the top surface of an organic layer. Since this electrode pattern must be formed after an organic layer is formed, only the vapor deposition method with low pattern formation accuracy is available. It makes it difficult to form homogenous and fine pixels. In a production method of an organic light emitting element in this invention, after forming a first electrode composed of a transparent electrode and a metal layer, an organic layer coats the transparent electrodes exposed by removing those portions of a metal layer corresponding to pixels, a second electrode is formed on the organic layer. In this method, the pixel formation accuracy depends on only a metal layer removing accuracy. Since the metal layer is removed before the organic layer is formed, the photolithographic technique can be applied to enable homogeneous and fine pixels to be formed.